

Jagannath Panigrahi

List of Publications by Year in descending order

Source: <https://exaly.com/author-pdf/7441596/publications.pdf>

Version: 2024-02-01

17
papers

324
citations

840119

11
h-index

940134

16
g-index

17
all docs

17
docs citations

17
times ranked

459
citing authors

#	ARTICLE	IF	CITATIONS
1	Growth and luminescence characteristics of zinc oxide thin films deposited by ALD technique. Journal of Luminescence, 2021, 233, 117797.	1.5	12
2	Effect of ALD window on thermal ALD deposited HfO _x /Si interface for silicon surface passivation. Materials Today: Proceedings, 2021, 46, 5761-5765.	0.9	1
3	Progress on the intrinsic a-Si:H films for interface passivation of silicon heterojunction solar cells: A review. Journal of Non-Crystalline Solids, 2021, 574, 121166.	1.5	24
4	Nanocrystalline silicon thin film growth and application for silicon heterojunction solar cells: a short review. Nanoscale Advances, 2021, 3, 3373-3383.	2.2	26
5	Importance of precursor delivery mechanism for Tetra-kis-ethylmethylaminohafnium/water atomic layer deposition process. Thin Solid Films, 2019, 692, 137629.	0.8	9
6	Enhanced field effect passivation of c-Si surface via introduction of trap centers: Case of hafnium and aluminium oxide bilayer films deposited by thermal ALD. Solar Energy Materials and Solar Cells, 2018, 188, 219-227.	3.0	11
7	Crystalline silicon surface passivation by thermal ALD deposited Al doped ZnO thin films. AIP Advances, 2017, 7, .	0.6	16
8	Atomic layer deposited dielectric and/or semiconducting oxide bilayers for crystalline silicon surface passivation. Energy Procedia, 2017, 124, 302-306.	1.8	3
9	Study of AlIn2</math>/O3</math>/ZnO multilayers for silicon surface passivation. , 2016, , .		0
10	Plasma assisted atomic layer deposited hafnium oxide films for silicon surface passivation. RSC Advances, 2016, 6, 97720-97727.	1.7	18
11	Impedance spectroscopy of crystalline silicon solar cell: Observation of negative capacitance. Solar Energy, 2016, 136, 412-420.	2.9	32
12	Silicon surface passivation using thin HfO ₂ films by atomic layer deposition. Applied Surface Science, 2015, 357, 635-642.	3.1	47
13	Influence of deposition temperature of thermal ALD deposited Al ₂ O ₃ films on silicon surface passivation. AIP Advances, 2015, 5, .	0.6	57
14	Effect of low thermal budget annealing on surface passivation of silicon by ALD based aluminum oxide films. Physical Chemistry Chemical Physics, 2014, 16, 21804-21811.	1.3	21
15	Synthesis of nano ZnO thin film on Al foil by rf glow discharge plasma and its effect on E. coli and P. aeruginosa. Applied Physics A: Materials Science and Processing, 2012, 108, 577-585.	1.1	2
16	Radio frequency plasma enhanced chemical vapor based ZnO thin film deposition on glass substrate: A novel approach towards antibacterial agent. Applied Surface Science, 2011, 258, 304-311.	3.1	40
17	Probing the effect of nitrogen gas on electrical conduction phenomena of ZnO and Cu-doped ZnO thin films prepared by spray pyrolysis. Ionics, 2011, 17, 741-749.	1.2	5